

IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A device manufacturing method comprising:  
providing ~~a an immersion~~ liquid between a substrate and at least a portion of a projection system of a lithographic projection apparatus, wherein a non-radiation sensitive material is carried by said substrate, said non-radiation sensitive material being at least partially transparent to radiation, ~~and being of a different material than said immersion liquid,~~ said non-radiation sensitive material being provided over at least a part of a radiation sensitive layer of said substrate, and said non-radiation sensitive material having a thickness of at least 5  $\mu\text{m}$ ; and  
projecting a patterned beam of radiation, through said ~~immersion~~ liquid, onto a target portion of said substrate using said projection system.
2. (Currently Amended) A method according to claim 1, wherein ~~said non-radiation sensitive material has a thickness and said radiation has a wavelength and said thickness is greater than said wavelength.~~
3. (Canceled)
4. (Currently Amended) A method according to claim ~~[[3]]~~ 1, wherein said non-radiation sensitive material has a thickness one of at least 10  $\mu\text{m}$  and at least 20  $\mu\text{m}$ .
5. (Currently Amended) A method according to claim 1, wherein said non-radiation sensitive material has a first refractive index and said ~~immersion~~ liquid has a second refractive index, and said first refractive index is within 0.2 of said second refractive index.
6. (Original) A method according to claim 5, wherein said first refractive index is one of within 0.1 of and substantially the same as said second refractive index.
7. (Original) A method according to claim 1, wherein said non-radiation sensitive material has a refractive index in the range of 1.0 to 1.7.

8. (Currently Amended) A method according to claim 1, wherein said non-radiation sensitive material is substantially insoluble in and unreactive with said ~~immersion~~ liquid.

9. (Original) A method according to claim 1, wherein a further protective material is present between said radiation sensitive layer and said non-radiation sensitive layer.

10. (Currently Amended) A method according to claim 1, wherein the non-radiation sensitive layer is of a thickness effective to substantially reduce the effect of ~~at least one of bubbles, and particles, or both bubbles and particles,~~ in said ~~immersion~~ liquid on the quality of the patterned beam impinging on the radiation sensitive layer.

11. (Original) A method according to claim 1, further comprising at least partly coating said radiation sensitive layer of said substrate with said non-radiation sensitive material.

12. (Withdrawn) A substrate for use in a lithographic projection apparatus, the substrate being at least partly covered by a radiation sensitive layer, the radiation sensitive layer being at least partly covered with a non-radiation sensitive material which is at least partly transparent to said radiation and being of a different material than an immersion liquid through which a patterned beam of said radiation of the lithographic projection apparatus is projected onto a target portion of said substrate.

13. (Withdrawn) A substrate according to claim 12, wherein said non-radiation sensitive material has a thickness and said radiation has a wavelength and said thickness is greater than said wavelength.

14. (Withdrawn) A substrate according to claim 12, wherein said non-radiation sensitive material has a thickness of at least 5  $\mu\text{m}$

15. (Withdrawn) A substrate according to claim 14, wherein said non-radiation sensitive material has a thickness of one of at least 10  $\mu\text{m}$  and at least 20  $\mu\text{m}$ .

16. (Withdrawn) A substrate according to claim 12, wherein said non-radiation sensitive material has a first refractive index and said immersion liquid has a second refractive index, and said first refractive index is within 0.2 of said second refractive index.
17. (Withdrawn) A substrate according to claim 16, wherein said first refractive index is one of within 0.1 of and substantially the same as said second refractive index.
18. (Withdrawn) A substrate according to claim 12, wherein said non-radiation sensitive material has a refractive index in the range of 1.0 to 1.7.
19. (Withdrawn) A substrate according to claim 12, wherein a further protective material is present between said radiation sensitive layer and said non-radiation sensitive layer.
20. (Withdrawn) A substrate according to claim 12, wherein said non-radiation sensitive material is substantially insoluble in and unreactive with said immersion liquid.
21. (Withdrawn) A substrate according to claim 12, wherein the non-radiation sensitive layer is of a thickness effective to substantially reduce the effect of at least one of bubbles and particles in said immersion liquid on the quality of a patterned beam impinging on the radiation sensitive layer.
22. (Currently Amended) A device manufacturing method comprising:  
providing a ~~an immersion~~-liquid, between a substrate and at least a portion of a projection system of a lithographic projection apparatus, to a non-radiation sensitive material on said substrate, said non-radiation sensitive material, which is at least partially transparent to radiation, provided over at least a part of a radiation sensitive layer of said substrate and having a thickness effective to substantially reduce the effect of ~~at least one of bubbles, and particles, or both bubbles and particles,~~ in said ~~immersion~~-liquid on the quality of a patterned beam impinging on the radiation sensitive layer; and  
projecting a patterned beam of radiation, through said ~~immersion~~-liquid, onto a target portion of said substrate using said projection system.

23. (Original) A method according to claim 22, wherein said thickness is greater than a wavelength of said radiation.

24. (Original) A method according to claim 22, wherein said thickness is at least 5  $\mu\text{m}$ .

25. (Original) A method according to claim 24, wherein said thickness is one of at least 10  $\mu\text{m}$  and at least 20  $\mu\text{m}$ .

26. (Currently Amended) A method according to claim 22, wherein said non-radiation sensitive material has a first refractive index and said ~~immersion~~-liquid has a second refractive index, and said first refractive index is within 0.2 of said second refractive index.

27. (Original) A method according to claim 26, wherein said first refractive index is one of within 0.1 of and substantially the same as said second refractive index.

28. (Original) A method according to claim 22, wherein said non-radiation sensitive material has a refractive index in the range of 1.0 to 1.7.

29. (Currently Amended) A method according to claim 22, wherein said non-radiation sensitive material is substantially insoluble in and unreactive with said ~~immersion~~ liquid.

30. (Original) A method according to claim 22, wherein a further protective material is present between said radiation sensitive layer and said non-radiation sensitive layer.

31. (Original) A method according to claim 22, further comprising at least partly coating said radiation sensitive layer of said substrate with said non-radiation sensitive material.